

REMARKS

Claims 1-4 and 6-19 are pending in this application, with claims 1-2 and 6-18 currently withdrawn. By this Amendment, claims 3 and 4 are amended to further define the presently claimed subject matter and are supported by at least page 11, lines 3-14, page 29, lines 5-19, page 29, lines 21-24, page 30, lines 20-28 and Figures 20a-20c of the present specification. Claim 19 is added and is supported by at least page 11, lines 3-14, page 29, lines 5-19, page 29, lines 21-24, page 30, lines 20-28 and Figures 20a-20c of the present specification. Claim 5 is canceled. No new matter is added by this Amendment.

I. Allowable Subject Matter

Applicants thank the Examiner for the indication that claim 4 would be allowable if the rejection under 35 U.S.C. §112, second paragraph, is overcome. Because the rejection is overcome for the reasons described below, claim 4 is in condition for allowance.

II. Amendments to the Specification

The Patent Office objected to the Abstract of the disclosure because it allegedly failed to recite process steps. Attached herewith is a substitute Abstract that includes process steps.

Withdrawal of the objection is respectfully requested.

III. Claim Amendments

Applicants respectfully point out that each of the amendments to claims 3 and 4 and new claim 19 are supported by the paragraphs set forth above. Applicants attach herewith this Amendment an Informational Figure to provide the Examiner with a broad representation of the claimed embodiments. Applicants submit that the Informational Figure should not be considered new matter by the Patent Office as Applicants are only attaching it for the Examiner's convenience.

IV. Rejection Under 35 U.S.C. §112, Second Paragraph

Claims 3-5 were rejected under 35 U.S.C. §112, second paragraph, as allegedly being indefinite. The Patent Office alleged that the nature and the extent of the mixing in claims 3 and 4 was allegedly unclear. Applicants have deleted the term "mixed" from claims 3 and 4. Applicants thus submit that claims 3-5 are definite.

Withdrawal of the rejection is respectfully requested.

V. Rejection Under 35 U.S.C. §102(e)

Claims 3 and 5 were rejected under 35 U.S.C. §102(e) as allegedly being anticipated by U.S. Patent No. 6,287,649 ("Fukushima"). Applicants respectfully disagree.

The Patent Office alleged that Fukushima describes a process where (1) a substrate is (1) coated with a metal film and subsequently coated with a photo-resist compound, (2) the photo-resist compound is patterned on the substrate by ultraviolet (UV) radiation, (3) the non-masked and masked areas of the photo-resist compound are first removed followed by the removal of the non-masked areas of the metal and (4) the treated substrate is immersed in a thiol-containing solution. Applicants respectfully disagree.

Fukushima describes that the perpendicular alignment layer 31 (i.e., the sulfur film) on the metal layer 33 is placed in a liquid crystal display device as a means for controlling the alignment of liquid crystal molecules. See Fukushima, col. 8, lines 11-45.

In contrast, Applicants have amended claim 3 to recite a method for manufacturing a substrate, comprising the steps of: (1) forming a metal layer on a base, (2) removing a part of the metal layer by supplying energy to form a pattern non-formation region comprised of the metal layer pattern non-formed region and a pattern formation region comprised of a metal layer pattern formed region and a base exposed region, (3) forming a sulfur compound film on the metal layer pattern unformed region and the metal layer pattern formed region by immersing the base in a liquid containing a sulfur compound, and (4) forming a thin film

pattern on the pattern formation region by applying a fluid to the pattern formation region that exhibits a non-affinity to the sulfur compound film and an affinity to the base.

Fukushima does not describe the step of forming a thin film pattern on the pattern formation region by applying a fluid to the pattern formation region that exhibits a non-affinity to the sulfur compound film and an affinity to the base as described in claim 3. As such, Fukushima does not anticipate the subject matter of claim 3.

Withdrawal of the 35 U.S.C. §102(e) rejection is respectfully requested.

Furthermore, Fukushima does not describe forming a thin film pattern on the pattern formation region by applying the fluid to the pattern formation region that exhibits an affinity to the sulfur compound film and a non-affinity to the base as recited in claim 19. For this reason, Fukushima also does not anticipate the subject matter of claim 19.

VI. Rejoinder

Applicants submit that upon allowance of elected claims 3-4 and 19, withdrawn claims 1-2 and 6-18 should be rejoined and similarly allowed..

VII. Conclusion

In view of the foregoing, it is respectfully submitted that this application is in condition for allowance. Favorable reconsideration and prompt allowance of claims 1-4 and 6-19 are earnestly solicited.

Should the Examiner believe that anything further would be desirable in order to place this application in even better condition for allowance, the Examiner is invited to contact the undersigned at the telephone number set forth below.

Respectfully submitted,



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Attachments:

Amended Abstract
Informational Figure

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